In the Claims

Claims 1-15 (canceled).

Claim 16 (previously presented): A PVD target having a sidewall proximate a sputtering face, wherein the sidewall forms a lateral periphery of the target, the target comprising:

a pattern of curved projections along the sidewall which form cavities that open laterally along the sidewall; and

bead-blast-formed microstructures on the curved projections.

Claim 17 (original): The target of claim 16 wherein the target is part of a target/backing plate construction.

Claim 18 (original): The target/backing plate construction of claim 17 wherein the backing plate has a sidewall and wherein the pattern of curved projections extends along the sidewall of the backing plate.

Claim 19 (original): The target/backing plate construction of claim 18 wherein the backing plate has a flange and wherein the pattern of curved projections extends along the flange of the backing plate.

Claim 20 (original): The target of claim 16 wherein the curved projections have bases, wherein the sidewall has a surface extending between the bases of the curved projections, and wherein the curved projections have a maximum height above the sidewall surface of from about 0.0001 inches to about 0.01 inches.

Claim 21 (original): The target of claim 16 wherein a periodic repeat of the curved projections across the sidewall occurs in a distance of from about 0.0001 inches to about 1 inch.

Claim 22 (cancelled).

Claim 23 (original): The target of claim 16 wherein the sputtering surface is defined as an upper surface; and wherein the cavities open upwardly.

Claim 24 (original): The target of claim 16 wherein the sputtering surface is defined as an upper surface; and wherein the cavities open downwardly.

Claim 25 (original): The target of claim 16 wherein the sputtering surface is defined as an upper surface; and wherein the cavities open sidewardly.

Claim 26 (previously presented): The target of claim 16 further comprising a flange spaced from the sputtering face by the sidewall, the flange having a surface, and wherein the pattern of curved projections extends along at least a portion of the surface of the flange.

Claim 27 (original): A PVD target/backing plate construction having a sidewall proximate a sputtering face, comprising:

a repeating pattern of receptacles along the sidewall, the receptacles having inner surfaces along an interior periphery of the receptacles; and

microstructures on the inner surfaces of the receptacles.

Claim 28 (original): The target/backing plate construction of claim 27 wherein a portion of the sidewall is comprised by the target, and wherein the pattern of receptacles is along the portion of the sidewall comprised by the target.

Claim 29 (original): The target/backing plate construction of claim 28 wherein a portion of the sidewall is comprised by the backing plate, and wherein the pattern of receptacles is along the portion of the sidewall comprised by the backing plate.

Claim 30 (original): The target/backing plate construction of claim 27 wherein a portion of the sidewall is comprised by the backing plate, and wherein the pattern of receptacles is along the portion of the sidewall comprised by the backing plate.

Claim 31 (original): The target/backing plate construction of claim 27 wherein the receptacles are defined by bent projections extending from the sidewall; wherein the bent projections have bases, wherein the sidewall has a surface extending between the bases of the bent projections, and wherein the bent projections have a maximum height above the sidewall surface of from about 0.0001 inches to about 0.01 inches.

Claim 32 (original): The target/backing plate construction of claim 31 wherein a periodic repeat of the bent projections occurs in a distance of from about 0.0001 inches to about 1 inch.

Claim 33 (original): The target/backing plate construction of claim 27 wherein the microstructures correspond to bead-blasted structures.

Claim 34 (previously presented): The target/backing plate construction of claim 27 further comprising a flange spaced from the sputtering face by the sidewall, the flange having a surface, and wherein the repeating pattern of receptacles extends along at least a portion of the surface of the flange.

Claim 35 (previously presented): The target/backing plate construction of claim 34 wherein the microstructures are on the receptacles that extend along at least a portion of the surface of the flange.